

# VISIBLE PHOTOLUMINESCENCE FROM SI1-1 GET QUANTUM WELLS

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#### **ABSTRAC**

complexes and polyexcitons. Time resolved spectra at twice the band-gap have been excitons, free excitons or localized excitons, which are difficult to separate in the usual near multiexciton or dense e-h plasma processes from single exciton processes such as bound thermal chemical vapor deposition (RTCVD). This new luminescence clearly distinguishes obtained from our SiGe samples prepared by molecular beam epitaxy (MBE) as well as rapid luminescence originating from electron-hole droplets, biexcitons, bound multiexciton of luminescence at twice the band-gap has been previously used in Si to observe simultaneous recombination of two electron hole pairs yielding a single photon. Detection approximately equal to twice the SiGe band-gap energy. This luminescence is caused by the We have observed photoluminescence from strained SiGe quantum well layers at energies nfrared luminescence.

# INTRODUCTION

species. We have observed visible luminescence in a variety of SiGe samples proving that effect which, if it were allowed, would generate green photoluminescence from all excitoni visible photoluminescence. It is important to appreciate that this is not a non-linear optical pairs such as a biexciton. Ordinary bound excitons for example cannot give rise to any extremely unlikely and can occur only for a complex containing two or more electron hole photon with an energy close to twice the band gap. Such a recombination process is technique requires the simultaneous recombination of two electron hole pairs resulting in a identification of luminescence due to multiexcitonic species or dense plasmas[10,11]. This as has been shown for bulk Si the visible luminescence technique allows the unambiguous biexcitons can all play a role creating considerable complexity in the IR spectrum. However observed luminescence. Impurity bound excitons, free excitons, localized excitons and as time-resolved measurements indicate that several processes are responsible for the investigation of the luminescence as a function of excitation density and temperature as well quantum wells has been achieved by several groups in the past two years[1-9] Detailed biexcitons contribute significantly to the near edge luminescence from SiGe quantum wells The observation of infrared (IR) luminescence from quantum confined excitons in SiGe

# EXPERIMENTAL

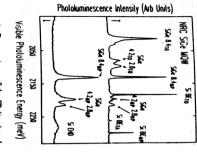
photoluminescence (PL) spectra were measured using a Bomem DA8 Fourier transform respectively. The IR luminescence was excited using an Ar ion laser and the are expected to be within  $\pm$  10% and  $\pm$  1 nm for the Ge fraction and SiGe thickness, nominal growth parameters are used here to describe the samples. The actual parameters (RTCVD) or by Molecular Beam Epitaxy (MBE), as described previously [12,6]. The interferometer with an InGaAs detector. The SiGe samples were grown either by Rapid Thermal Chemical Vapour Deposition

wavelength along the x-axis, time along the y-axis and intensity along z. computer a complete three dimensional manifold of the luminescence can be collected with combining the output from the timing electronics with that from the photomultiplier position a timing signal from the photomultiplier [13], and cavity dumping the Ti sapphire laser, time resolved measurements of the luminescence can be made with nanosecond resolution. By essential in order to observe the extremely weak visible PL [11]. Furthermore, by picking off collection capability of this photomultiplier, as well as its extremely low dark count, are Laboratories Mepsicron) mounted on the spectrometer camera port [13]. The parallel blazed at 500 nm and then imaged onto an imaging photomultiplier (ITT / Surface Science luminescence was dispersed by a single 3/4m spectrometer with a 300 groove/mm grating The visible luminescence was excited at 740 nm using a Ti sapphire laser. The visible

In order to reject the laser excitation a holographic rejection filter centered at 756 nm was used in conjunction with a stack of short pass glass filters optics were all enclosed in a light tight enclosure. The laser was filtered at the entrance of the enclosure using a long pass glass filter to remove any visible components from the beam The samples were immersed in superfluid liquid helium. The dewar, spectrometer and

well features in the IR after taking into account the factor of two difference in energy the visible. The features in the visible spectrum are found to line up with the NP quantum phonon replicas of the quantum well luminescence are also absent in the visible spectrum energy. For comparison purposes the IR spectrum at half the energy scale is plotted in the 8 4 nm is shown in Fig. 1. The spectrum clearly exhibits contributions from all three wells as Consequently, the intensity of phonon replicas should be much weaker than principal lines in electrons in opposite conduction band valleys resulting in zero net crystal momentum since the visible no-phonon (NP) transitions do not require the participation of a phonon substrate, which dominates the IR spectrum, is absent from the visible PL spectrum. The upper part of the figure. Note that the ordinary bound exciton (BE) luminescence from the well as a small contribution from the electron-hole droplet (EHD) in the substrate at higher [11]. Phonon less recombination can occur when the two constituent excitons have their The visible PL from an MBE SiGe sample with three quantum wells of width 2.8, 4.2 and

quantum well recombination mechanism under high excitation conditions close to linear over two orders of magnitude indicating that biexciton decay is the dominant Sample a) contains three quantum wells but only two are seen in luminescence. The visible luminescence intensity as a function of excitation density in this sample was found to be In Fig. 2 the visible and IR spectra of 6 different SiGe quantum well samples is shown



Infrared Photoluminescence Energy (meV)

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1125

Figure 1. Comparison of the IR (top) and visible (bottom) spectra of a 3 well (2.8, 4.2, 8.4 nm, 14% Ge) MBE sample. The arrows point to the corresponding energy scale. The sample temperature was × 1.7K. For the IR and visible spectra the excitation was × 50 mW / cm<sup>2</sup> at 514.5 nm and ×50 W / cm<sup>2</sup> at 740 nm respectively. Features labeled BE are bound exciton recombination from the Si substrate. Features labeled TO are TO phonon replicas of the corresponding no-phonon (NP) lines.

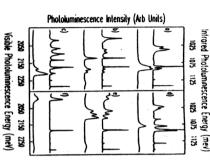


Figure 2. Comparison of the IR (upper) and visible (lower) spectra for 6 SiGe quantum well samples.

a) MBE, 28, 42, 8.4 nm, 14% Ge
b) MBE, 28, 42, 8.4 nm, 14% Ge
c) MBE, 84, 42, 28 nm, 14% Ge
d) MBE, 12 nm, 38% Ge
e) MBE, 12 nm, 38% Ge
e) MBE, 12 nm, 35% Ge

In other words the shallow alloy fluctuations are saturated with localized excitons at very low excitation densities in such samples (see Lenchyshyn et. al., these proceedings), so that at higher excitation the biexciton density increases linearly with excitation power. Sample b) is the same as the one presented in Fig. 1. Sample c) is similar to sample b), it also contains three wells of width 2.8, 4.2 and 8.4 nm. However, c) has the narrowest well closest to the substrate while b) has the widest well closest to the substrate. Since most of the excitons formed by the excitation originate in the substrate the well closest to the substrate is expected to have the greatest luminescence intensity. These expectations are borne out by the relative intensities of luminescence peaks shown in Fig. 2 b) and c). Sample d) has only a single very thin well which is 1.2 nm wide. Sample e) is a multiple quantum well sample in which all the well widths were intended to be the same. The spectra however shows three distinct peaks indicating that either the well width or the Ge fraction is not uniform. The last sample f) is a single quantum well RTCVD sample whereas the others were all grown by MBE. This indicates that biexciton processes are important in samples grown by both techniques.

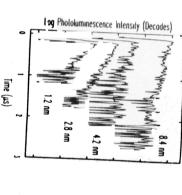


Figure 3 Biexciton lifetimes as determined from samples b) c) and d). The excitation used was cavity dumped 740 nm radiation with an average power of w 4W / cm² at a repetition rate of 250 Khz and a pulse width of ≈ 10 ns. The sample temperature was ≈ 1.7 K.

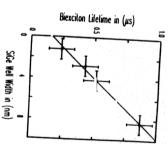


Figure 4. Biexciton lifetimes as a function of well width. The points are from the best fits to the data in Figure 3. The straight line is the best fit to the points.

By averaging together all counts over the spectral width of the individual peaks in the 3D luminescence manifold visible luminescence decay curves can be extracted for each well. The results are displayed in Fig. 3 and indicate that the biexciton lifetime decreases with decreasing well width. This is qualitatively as expected given the increased exciton-exciton recombination probability. The observed lifetime as a function of well width is shown in Fig. 4 where the lifetime has been determined by the best straight line fit to the data in Fig. 3. The values obtained for the biexciton lifetimes =0.5 µs are close to the fast lifetime components values obtained for the biexciton lifetimes =0.5 µs are close to the fast lifetime components observed in the IR quantum well luminescence under high excitation conditions in the same samples (Lenchyshyn et al., these proceedings).

## CONCLUSIONS

We have clearly observed visible luminescence from a variety of SiGe quantum well samples. These results prove that a major component of the quantum well luminescence under high excitation conditions and low sample temperatures is due to biexcitons. Biexciton lifetime measurements indicate that the biexciton lifetime decreases with decreasing quantum well width.

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